Supplementary Information

Controllable and Large-Scale Fabrication of Flexible ITO-free Electrochromic Devices by Crackle Pattern Technology

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Figure S1. Mechanism model of the formation process of the rectangular colloidal pattern.



Figure S2. Ag networks TCFs fabricated on different substrates.



Figure S3. SEM images of Ag networks film after 1000 cycles.



Figure S4. The relationship between ultrasonic treatment time and the R_s increasing of flexible Ag networks TCF and ITO film.



Figure S5. (a) SEM images of the controllable crackle patterns with different crackle width and density when the film thickness is 1 μ m; (b) the SEM images of the rows of crackle patterns in a fixed field of vision (0.5 mm width in SEM image).



Figure S6. The relationship between negative voltages and the transmittance of the flexible ECD in colored state.



Figure S7. The relationship between positive voltages and the transmittance of the flexible ECD in bleached state.



Figure S8. The relationship between the placing days of the flexible ECD in air and the optical modulations.



Figure S9. (a) Galvanostatic charge-discharge curves at different current densities; (b) cyclic charge and discharge curve for 40000 s.



Figure S10. The relationship between the bending cycles and optical modulation range of electrochromic device.